



Doc. 104

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Ted A. Loxley
Serial No. : 09/490,162
Filed : January 22, 2000
For: PROCESS AND APPARATUS FOR CLEANING SILICON WAFERS
Examiner : V. Simkovic
Group Art Unit : 2812

#11/DW/14
EDS
2/5/02
V. Vannall

Box AF
Assistant Commissioner for Patents
Washington, D.C. 20231

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AMENDMENT AFTER FINAL REJECTION

Please enter the following amendment to supplement the
amendment filed December 5, 2001:

Page 1, cancel the first paragraph and substitute the
following:

-- This application claims the benefit of my provisional
application Serial No. 60/116,940 filed January 23, 1999. --

R E M A R K S

No fee is required for the present amendment. A check
for \$180.00 is enclosed to cover the fee for the enclosed
information disclosure statement.

Six patent references are cited in the enclosed Form
PTO-1449 which may have some relevance. Copies of these
references are enclosed for the file.

The patents to Uzoh ('619) and Glass ('964) disclose
methods for use in integrated circuit fabrication wherein an
ionic conductive aqueous electrolyte wets and covers the

substrate surface and wherein electrodes are employed to cause the flow of an ionic current to the substrate surface. In patent '619 the electric current is controlled to reduce the probable damage to the delicate microelectronic components at the wafer surface. In patent '964 the interfacial tension at the interface is controlled by applying an electrical potential difference of about 0.1 to about 1.0 volt (e.g., see pages 2, 9 and 13).

Entry of the amendment is requested.

Respectfully submitted,



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January 15, 2002